L Number	Hits	Search Text	DB	Time stamp
1	22	(deflect$ with (light or radiation) with cantilever) and (silicon with (mirror or reflector))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:15
2	38	(deflect$ with (light or radiation) with cantilever) and (silicon with etch$) and (mirror or reflector or micromirror or micro?mirror)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:18
3	152	(deflect$ with (light or radiation)) and cantilever$ and (silicon with etch$) and (mirror or reflector or micromirror or micro?mirror)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:28
4	7	("4182544" | "4657339" | "4669817" | "4674828" | "4675521" | "4684208" | "4705349").PN.	USPAT	2004/02/11 09:22
5	2	("4182544").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:27
6	457	(deflect$ with (light or radiation)) and fix$3 and (silicon with etch$) and (mirror or reflector or micromirror or micro?mirror)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:28
7	403	(reflect$ with (light or radiation)) and cantilever$ and (silicon with etch$) and (mirror or reflector or micromirror or micro?mirror)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:43
8	113	((reflect$ with (light or radiation)) and cantilever$ and (silicon with etch$) and (mirror or reflector or micromirror or micro?mirror)) and anisotrop$ and fiber	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:40
9	86	access$ with internal$ with position$ with (plane or mirror or reflector or deflector)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:41
10	77	((reflect$ or deflect$) with (light or radiation)) and (intersect$ with (passage or channel))and (silicon with etch$) and (mirror or reflector or micromirror or micro?mirror)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/11 09:44
-	2	("6008128").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 09:09

-	576	(359/223).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/07 17:14
-	255	(359/298).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/07 17:14
-	505	(359/838).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/07 17:14
-	88	(205/116).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/07 17:15
-	135	((359/223).CCLS.) and silicon$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 09:20
-	85	((359/298).CCLS.) and silicon$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 10:21
-	66	((359/838).CCLS.) and silicon$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 10:30
-	8	((205/116).CCLS.) and silicon$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 10:33
-	421	silicon and mirror and bulk and monolith$ and crystal$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 10:43
-	46	(silicon and mirror and bulk and monolith$ and crystal$4) and inlet and outlet	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 10:37

-	31	silicon and mirror and bulk and monolith$ and (crystal$4 adj plane)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 10:51
-	89	(single adj crystal adj silicon) and mirror and (crystal$4 adj plane)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 08:28
-	692	(single adj crystal adj silicon) and mirror and plane and etch$3	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 11:43
-	309	((single adj crystal adj silicon) and mirror and plane and etch$3) and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 11:09
-	101	(((single adj crystal adj silicon) and mirror and plane and etch$3) and anisotrop$) and fiber and optic$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 11:10
-	121	(single and crystal and silicon) and mirror and plane and etch$3 and anisotrop$ and fiber and optic$4 and internal$2	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 14:11
-	256	single and crystal$4 and silicon and mirror and etch$3 and stripe and intersect$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 14:25
-	118	(single and crystal$4 and silicon and mirror and etch$3 and stripe and intersect$4) and internal	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 11:58
-	373	(single near crystal$4 near silicon) with mirror	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 12:05
-	39	((single near crystal$4 near silicon) with mirror) and (fiber near optic$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 12:06

-	3645	digital and mirror and device and silicon and crystal$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 14:12
-	168	(digital and mirror and device and silicon and crystal$4) and bulk and monolith$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 14:12
-	341	silicon and mirror and etch$3 and stripe and intersect$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 14:36
-	2259	silicon and mirror and pattern$3 and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 14:37
-	403	(single adj crystal$4 adj silicon) and mirror and pattern$3 and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 15:20
-	0	(bulk with (single adj crystal$4 adj silicon)) and (mirror near pattern$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 15:22
-	20	silicon and (mirror near pattern$3) and (anisotrop$ near etch$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 15:34
-	16	silicon and ((mirror near pattern$3) with array$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 15:39
-	2585	(mirror with array$) and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:16
-	9	(mirror with array$) and (bulk with single with crystal$4 with silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 15:43

-	2	((mirror with array$) and silicon) and anisotrop$ and (bulk near crystal$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 15:44
-	2	monolithic adj bulk adj crystal adj silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:17
-	2	monolithic with bulk with crystal with silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:17
-	1586	monolithic and bulk and crystal and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:18
-	25	(monolithic and bulk and crystal and silicon) and (crystalline near plane)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:19
-	362	(monolithic and bulk and crystal and silicon) and (crystalline and plane)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:20
-	4	((monolithic and bulk and crystal and silicon) and (crystalline and plane)) and (micro?mirror or (micro adj mirror))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:20
-	109	((monolithic and bulk and crystal and silicon) and (crystalline and plane)) and mirror	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:41
-	4	silicon near mirror near array	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:42
-	1415	digital near (micromirror or micro?mirror or (micro adj mirror)) near device	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 16:43

-	350	(digital near (micromirror or micro?mirror or (micro adj mirror)) near device) and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 17:12
-	16	(digital near (micromirror or micro?mirror or (micro adj mirror)) near device) and (single adj crystal adj silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 17:14
-	3991	(mirror or reflect$) and (single adj crystal adj silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 17:16
-	240	((mirror or reflect$) and (single adj crystal adj silicon)) and bulk and monolith$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 17:42
-	148	anisotrop$ with silicon with array with etch$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 17:43
-	226	(anisotrop$ with silicon with process$) and (mirror or reflector)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 18:38
-	25	silicon and mirror and passage and (crystalline adj plane)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 18:42
-	42	(monolithic and bulk and crystal and silicon) and (mirror or reflector) and crystalline and plane and intersect$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/09/17 18:44
-	606	(359/223).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 08:10
-	290	(359/298).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 08:10

-	553	(359/838).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 08:10
-	88	(205/116).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 08:10
-	42	((359/223).CCLS.) and (mirror or reflector) and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/07 17:28
-	23	((359/298).CCLS.) and (mirror or reflector) and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/07 17:52
-	15	((359/838).CCLS.) and (mirror or reflector) and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/07 17:54
-	1	((205/116).CCLS.) and (mirror or reflector) and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/07 17:56
-	244	silicon and ((mirror or reflector) with anisotrop$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/10 08:20
-	2	westra.in. and silicon and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/10 08:21
-	101	westra.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/03/10 08:21
-	422	((bulk or (single near3 crystal$) or homogen$) near3 silicon) and (internal with (mirror or reflect$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:34

-	71	(((bulk or (single near3 crystal$) or homogen$) near3 silicon) and (internal with (mirror or reflect$))) and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 08:31
-	5	((bulk or (single near3 crystal$) or homogen$) near3 silicon) and (internal$2 with (mirror or reflect$) with etch$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:02
-	1	((bulk or (single near3 crystal$) or homogen$) near3 silicon) and (atom$6 with flat with (mirror or reflect$) with etch$4)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:04
-	6	((bulk or (single near3 crystal$) or homogen$) near3 silicon) and (atom$6 with flat with (mirror or reflect$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:07
-	0	((bulk or (single near3 crystal$) or homogen$) near3 silicon) and (atom$6 with flat with anisotrop$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:08
-	2	silicon same (atom$6 with flat with anisotrop$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:10
-	5	silicon same (atom$6 with flat) same anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:10
-	512	((bulk or (single near3 crystal$) or homogen$) near3 silicon) and ((internal or bur$3) with (mirror or reflect$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:13
-	356	(((bulk or (single near3 crystal$) or homogen$) near3 silicon) and ((internal or bur$3) with (mirror or reflect$))) and etch$4	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:14
-	69	(((bulk or (single near3 crystal$) or homogen$) near3 silicon) and ((internal or bur$3) with (mirror or reflect$))) and (etch$4 with plane)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 09:14

-	166	((bulk or crystal$ or homogen$) near3 silicon) and (internal with (mirror or reflect$ or deflect$)) and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 10:15
-	324	((bulk or crystal$ or homogen$) near3 silicon) and (integra$ with (mirror or reflect$ or deflect$)) and anisotrop$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 11:13
-	7	("4182544" | "4657339" | "4669817" | "4674828" | "4675521" | "4684208" | "4705349").PN.	USPAT	2003/07/30 11:04
-	642	silicon and (integra$ with (mirror or reflect$ or deflect$)) and (anisotrop$ with etch$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 11:16
-	182	(integra$ with (mirror or reflect$ or deflect$)) and (silicon with anisotrop$ with etch$3) and (hole or bore or passage)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 11:56
-	84	(silicon with (mirror or reflect$ or deflect$) with (micromachin$ or micro?machin$)) and (anisotrop$ with etch$3)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 11:58
-	35	(atom$6 near3 (smooth$4 or flat$4)) with etch$4 with silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 12:25
-	256	(atom$6 near3 (smooth$4 or flat$4)) and (mirror or reflect$ or deflect$) and etch$4 and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 12:26
-	35	((atom$6 near3 (smooth$4 or flat$4)) same (mirror or reflect$ or deflect$)) and etch$4 and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 12:31
-	52	(atom$6 near3 (smooth$4 or flat$4)) and (mirror or reflect$ or deflect$) and (anisotrop$ with etch$4) and silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/07/30 12:32
-	678	(359/223).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 10:52

-	339	(359/298).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 10:53
-	603	(359/838).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 10:53
-	89	(205/116).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 10:53
-	1340	(mirror or reflect$ or deflect$ or micromirror or (micro?mirror)) with internal$ with (fixed or stationary)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 13:13
-	4	((mirror or reflect$ or deflect$ or micromirror or (micro?mirror)) with internal$ with (fixed or stationary)) and (anisotrop$ with etch$) and ((bulk or (single with crystal$)) with silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 13:54
-	1340	(mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or micro adj mirror) with internal$ with (fixed or stationary)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 13:16
-	0	(mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or micro adj mirror) with internal$ with (expos$ with durface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 13:16
-	421	(mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or micro adj mirror) with internal$ with (expos$ with surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 13:16
-	149	((mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or micro adj mirror) with internal$ with (expos$ with surface)) and (inlet or passage or outlet)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:43
-	544	((bulk or (single with crystal$) or monolith$) with silicon) same (crystal$ with (mirror or reflect$) with surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 14:34

-	88	(((bulk or (single with crystal$) or monolith$) with silicon) same (crystal$ with (mirror or reflect$) with surface)) and (anisotrop$ near3 etch$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 14:35
-	7	(((bulk or (single with crystal$) or monolith$) with silicon) same (crystal$ with (mirror or reflect$) with surface)) and (total$ with internal$ with reflect$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 14:36
-	1094	((bulk or (single with crystal$) or monolith$) with silicon) same ((mirror or reflect$ or deflect$) with surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:00
-	204	(((bulk or (single with crystal$) or monolith$) with silicon) same ((mirror or reflect$ or deflect$) with surface)) and ((anisotrop$ near3 etch$) or (deep$3 with reactive$2 with etch$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 14:36
-	11	((((bulk or (single with crystal$) or monolith$) with silicon) same ((mirror or reflect$ or deflect$) with surface)) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))) and (total$ with internal$ with reflect$)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:43
-	253	(((bulk or (single with crystal$) or monolith$) with silicon) same ((mirror or reflect$ or deflect$) with surface)) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:12
-	8	(("5600741") or ("5487124") or ("5485538") or ("5757994")).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:03
-	35	((bulk or (single with crystal$) or monolith$) with silicon) same ((mirror or reflect$ or deflect$) with surface with (internal$ or cavity))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:11
-	468	((bulk or (single with crystal$) or monolith$) with silicon) and (((mirror or reflect$ or deflect$) with surface) with (internal$ or cavity))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:36
-	149	(((bulk or (single with crystal$) or monolith$) with silicon) and (((mirror or reflect$ or deflect$) with surface) with (internal$ or cavity))) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:23

-	47	((bulk or (single with crystal$) or monolith$) with silicon) and (((mirror or reflect$ or deflect$) with surface) with (internal$ or cavity)) and (guid$ with light)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:38
-	7242	((mirror or reflect$ or deflect$) with surface with silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:41
-	1112	(((mirror or reflect$ or deflect$) with surface with silicon)) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:56
-	1118	((mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or micro adj mirror) with surface with silicon) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:51
-	28	(((mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or micro adj mirror) with surface with silicon) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))) and (total$ with internal$ with reflect$) and (optic$4 with fiber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 15:44
-	112	((mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or micro adj mirror) with cavity with silicon) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:21
-	185	(embed$ or bur$3) with (mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or micro adj mirror) with silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:22
-	185	(embed$ or bur$3) with (mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or (micro adj mirror)) with silicon	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:55
-	45	((embed$ or bur$3) with (mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or (micro adj mirror)) with silicon) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:23
-	175	(coupl$ with (mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or (micro adj mirror)) with silicon) and (optic$4 with fiber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:29

-	7546	(mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or (micro adj mirror)) with silicon with (plane or surface)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:56
-	1163	((mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or (micro adj mirror)) with silicon with (plane or surface)) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 17:35
-	680	(((mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or (micro adj mirror)) with silicon with (plane or surface)) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))) and (cavity or internal$ or inside)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:58
-	270	((((mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or (micro adj mirror)) with silicon with (plane or surface)) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))) and (cavity or internal$ or inside)) and (optic$4 with fiber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:58
-	143	(((((mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or (micro adj mirror)) with silicon with (plane or surface)) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))) and (cavity or internal$ or inside)) and (optic$4 with fiber)) and switch$ and coupl$	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 16:59
-	246	(anisotrop$ with (reactive$2 with ion with etch$)) same groove	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 17:47
-	53	((anisotrop$ with (reactive$2 with ion with etch$)) same groove) and ((bulk or (single with crystal$) or monolith$) with silicon)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 17:39
-	14	((anisotrop$ with (reactive$2 with ion with etch$)) same groove) and silicon and (optic$4 with fiber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 17:39
-	20	(anisotrop$ with (reactive$2 with ion with etch$)) and v?groove and silicon and (optic$4 with fiber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 17:51
-	105	anisotrop$ and (reactive$2 with ion with etch$) and v?groove and silicon and (optic$4 with fiber)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 17:51

-	195	(((mirror or reflect$ or deflect$ or micromirror or (micro?mirror) or micro adj mirror) with surface with silicon) and ((anisotrop$ near3 etch$) or (reactive$2 with ion with etch$))) and (inlet or passage or outlet)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2004/02/10 18:27